

## ABSTRACT OF THE DISCLOSURE

### AQUEOUS CLEANING COMPOSITION AND METHOD FOR USING SAME

An aqueous-based composition and method comprising same for removing residues such as without limitation post-ashed and/or post-etched photoresist from a substrate is described herein. In one aspect, there is provided a composition for removing residues comprising: water; at least one selected from a hydroxylamine, a hydroxylamine salt compound, and mixtures thereof; and a corrosion inhibitor wherein the composition is substantially free of an added organic solvent and provided that the corrosion inhibitor does not contain a water soluble organic acid.